Università degli Studi

di Trento



FE65-p2 / CHIPIX65 3D sensor layout

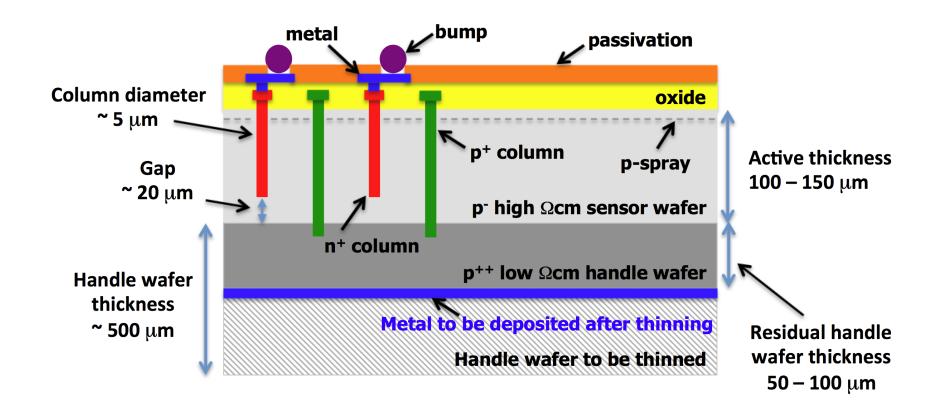
Gian-Franco Dalla Betta

University of Trento and TIFPA INFN, Trento, Italy



3D sensor cross section

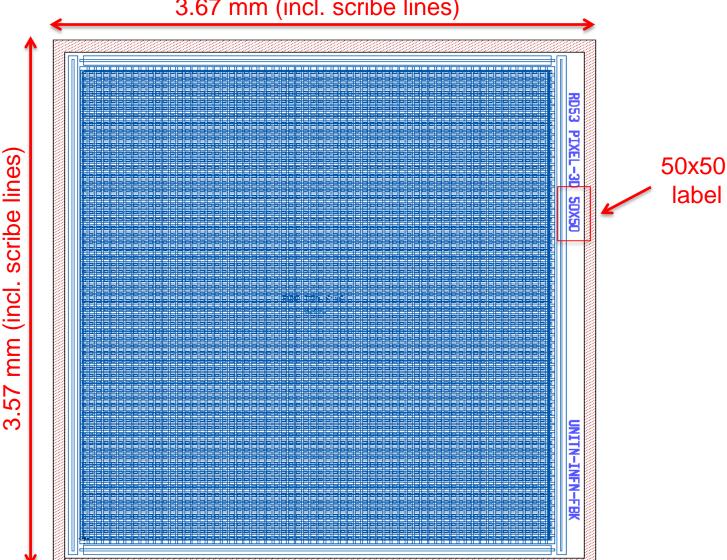
- The sensors were fabricated at FBK on Silicon Silicon Direct Wafer Bonded substrates with a single-sided process. The active layer is 130 μm thick.
- On these prototypes the handle wafer was not thinned.





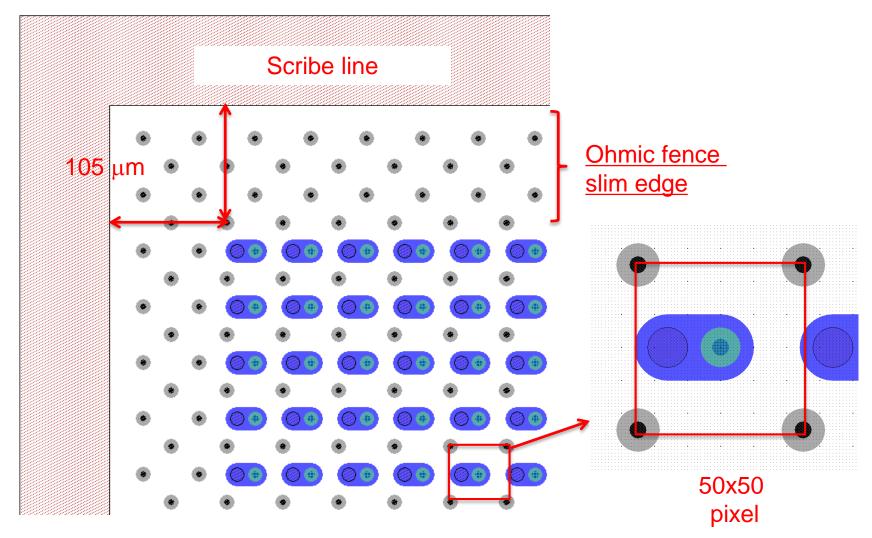
CHIPIX65 3D sensors (1): 50x50

3.67 mm (incl. scribe lines)



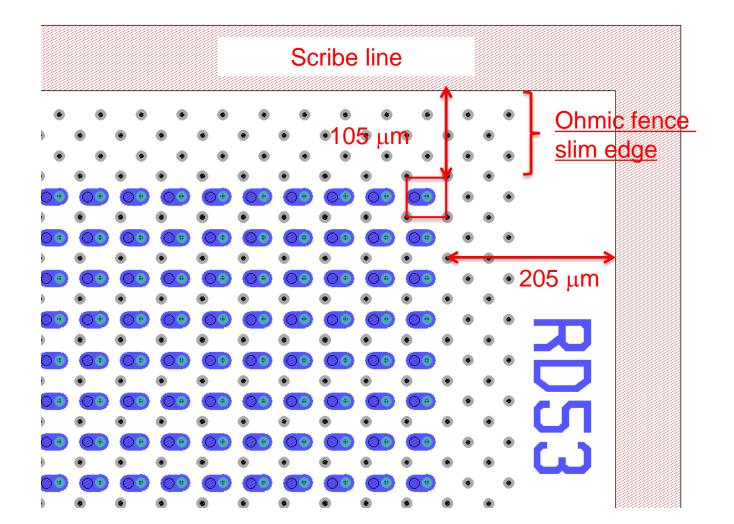


CHIPIX65 3D sensors (2): 50x50 Top left corner details





CHIPIX65 3D sensors (3): 50x50 Top right corner details

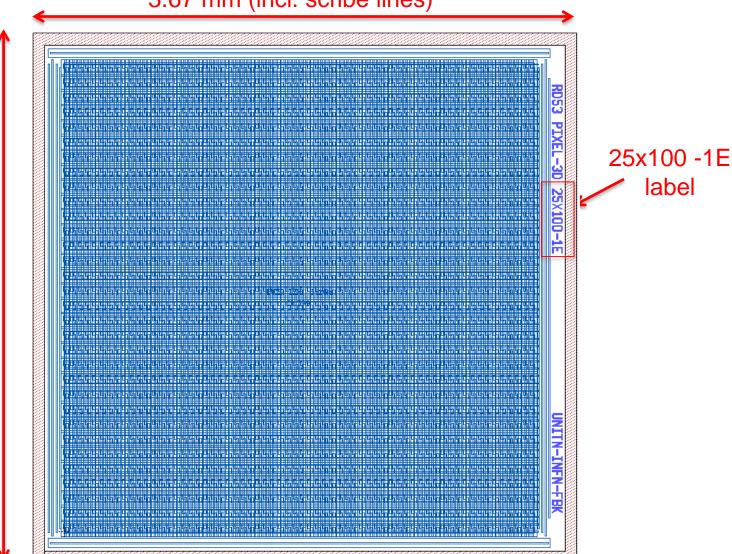


mm (incl. scribe lines



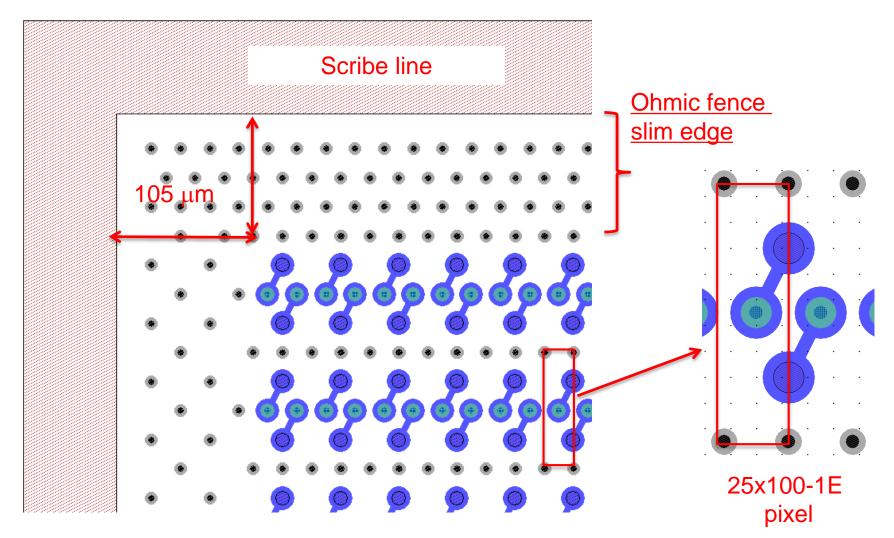
CHIPIX65 3D sensors (4): 25x100-1E

3.67 mm (incl. scribe lines)





CHIPIX65 3D sensors (5): 25x100-1E Top left corner details





CHIPIX65 3D sensors (6): 25x100-1E Top right corner details

